

# Cardiovascular Metallic Implants: Corrosion, Surface Characterization, and Nickel Leaching

March 8-9, 2012

FDA, Silver Spring, MD

# Workshop Organizing Committee

## Program Committee:

- Ashley Boam
- Ronald Brown
- Kenneth Cavanaugh
- Matthew Di Prima\*  
([matthew.diprima@fda.hhs.gov](mailto:matthew.diprima@fda.hhs.gov))
- Rosalie Elespuru
- Jennifer Goode\*  
([jennifer.goode@fda.hhs.gov](mailto:jennifer.goode@fda.hhs.gov))
- Nicole Ibrahim\*  
([nicole.ibrahim@fda.hhs.gov](mailto:nicole.ibrahim@fda.hhs.gov))
- Srinidhi Nagaraja
- David Saylor\*  
([david.saylor@fda.hhs.gov](mailto:david.saylor@fda.hhs.gov))
- Erica Takai\*  
([erica.takai@fda.hhs.gov](mailto:erica.takai@fda.hhs.gov))
- Terry Woods

## Logistics:

- Susan Monahan
- Nicole Ibrahim
- Lisa Lim
- Erica Takai

Special thanks to Dorothy Abel  
and Donna Lochner

\*moderators



# Workshop Logistics

## Format:

- Limited presentations (sessions 1-3)
- Moderated discussion with lead discussants
  - Limited audience participation as time permits
  - Strict time limits for discussions



## Ground Rules:

- Tent cards upright to comment
- State your name each time before you comment

## Other:

- Box lunch, snacks, and coffee available for purchase
- Visitors can only access Building 31 (workshop site)

# Workshop Agenda

## Day 1:

- Corrosion
- Surface Characterization

## Day 2:

- Nickel Leach and Toxicity
- Summary Session: Potential Testing Paradigms

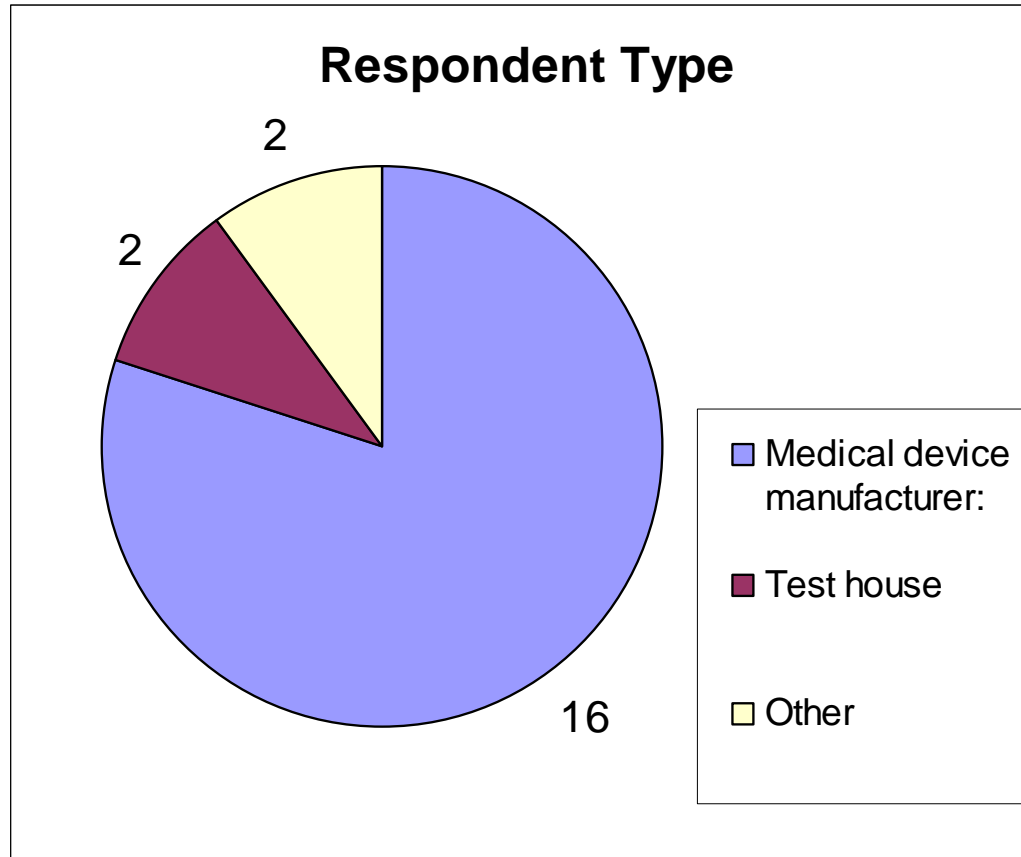
# Workshop Objectives

To provide a forum for the discussion of:

- Methods for corrosion assessments, surface characterization techniques, and nickel leach testing used to evaluate the suitability of metallic cardiovascular implant devices
- Limitations of these tests to predict actual in vivo performance
- Utility/circumstances when these tests should be considered
- Potential testing paradigms, including what could be used as acceptance criteria for each test



# Pre-Workshop Homework Respondents



total respondents = 20 (including partial responses)

**Note:** Standards discussed in the workshop/HW are those commonly used for device characterization; however, other methods may also be appropriate